

ABSTRACT

FERROMAGNETIC MATERIAL SPUTTERING TARGET

5 Provided is a ferromagnetic material sputtering target having a metal
composition comprising 5 mol% or more of Pt and the balance of Co, wherein the
target has a structure including a metal base (A) and a phase (B) of a Co-Pt alloy
containing 40 to 76 mol% of Pt in the metal base (A). Further provided is a
ferromagnetic material sputtering target having a metal composition comprising 5
10 mol% or more of Pt, 20 mol% or less of Cr, and the balance of Co, wherein the
target has a structure including a metal base (A) and a phase (B) of a Co-Pt alloy
containing 40 to 76 mol% of Pt in the metal base (A). The present invention
provides a ferromagnetic material sputtering target that can improve the leakage
magnetic flux to allow stable discharge with a magnetron sputtering device.

15 [Selected Drawing] Figure 1